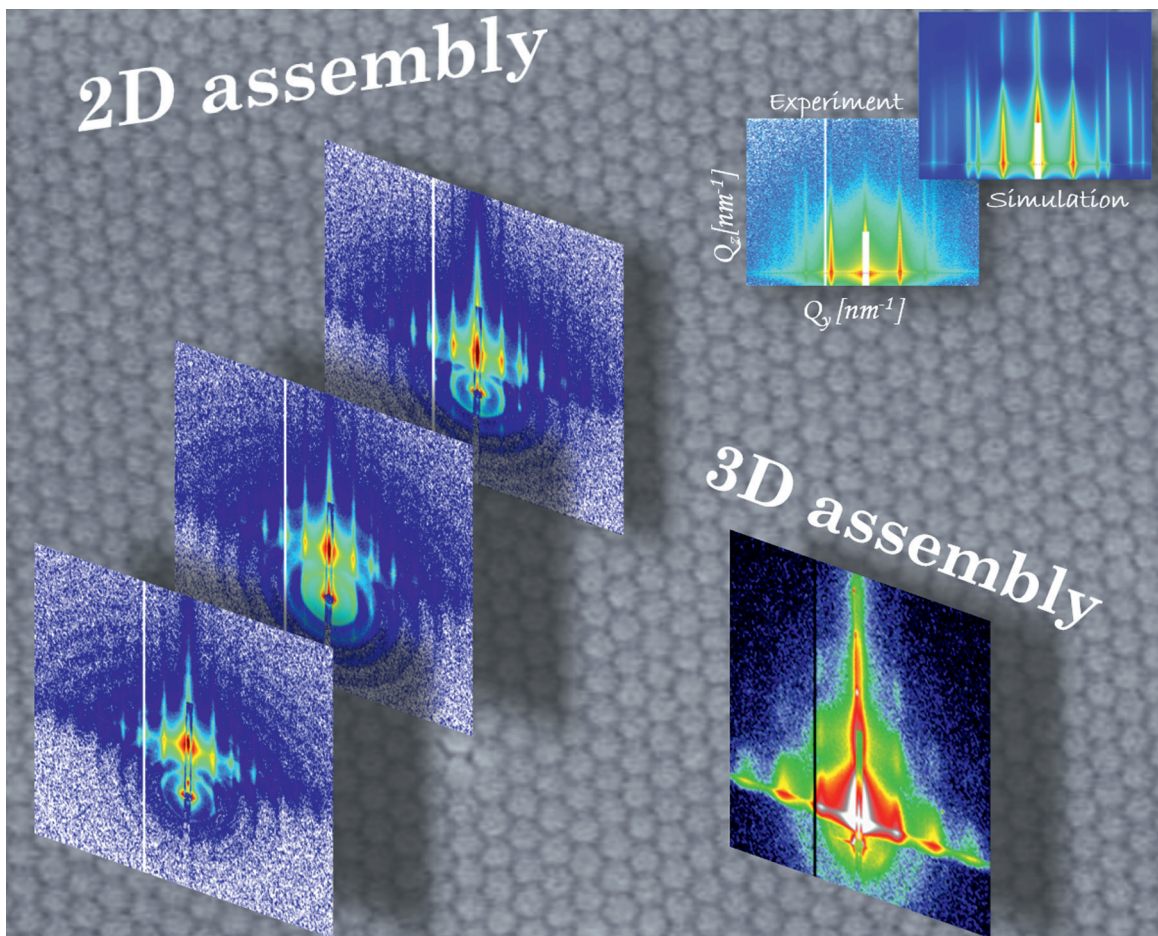




Nanoparticle assemblies: Order by self-organization and collective magnetism

Asma Qdemat

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